

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application No.	10/540,056
	Filing Date	June 22, 2005
	First Named Inventor	Sato et al.
	Art Unit	1795
(Multiple sheets used when necessary)	Examiner	John S Y Chu
SHEET 1 OF 1	Attorney Docket No.	SHIGA7.021APC

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹
	1	JP 2004-012513	01-15-2004	Matsushita Elec. Ind. Co., Ltd.		√
	2	JP 2002-373845	12-26-2002	Sony Corp.		√
	3	EP 1357428	10-29-2003	Murakami et al.		

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹
	4	UTSUMI, "Low-energy E-Beam Proximity Lithography (LEEPL): Is the Simplest the Best?", Japanese Journal of Applied Physics, Vol. 38, Part 1, No. 12B, pp. 7046-7051 (1999)	
	5	Decision to Grant a Patent issued on August 26, 2008 on the counterpart Japanese Application No. 2003-334029 of the related Application No. 10/572,709.	

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Examiner Signature	Date Considered
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

T¹ - Place a check mark in this area when an English language Translation is attached.